## REPORT DOCUMENTATION PAGE

AFRL-SR-AR-TR-03-

Public reporting burden for this collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searchin the collection of information. Send comments regarding this burden estimate or any other aspect of this collection of information, including suggestic Operations and Reports, 1215 Jefferson Davis Highway, Suite 1204, Arlington, VA 22202-4302, and to the Office of Management and Rudnet, Paperwir

0371

ving

1. AGENCY USE ONLY (Leave blank)

4. TITLE AND SUBTITLE

2. REPORT DATE

3. REPORT TYPE AND DATES COVERED

01 Apr 2000 - 30 Jun 2001 Final Report

5. FUNDING NUMBERS

6

Acquisition of Single and Double Crystal X-Ray Topograph System

61103D 3484/US

6. AUTHOR(S)

Dr Skowronski

7. PERFORMING ORGANIZATION NAME(S) AND ADDRESS(ES) CARNEGIE-MELLON UNIVERSITY

OFFICE OF RESEARCH CONTRACTS

5000 FORBES AVENUE

PITTSBURGH PA 15213-3890

9. SPONSORING/MONITORING AGENCY NAME(S) AND ADDRESS(ES)

AFOSR/NE

4015 WILSON BLVD

**SUITE 713** 

**ARLINGTON VA 22203** 

11. SUPPLEMENTARY NOTES

8. PERFORMING ORGANIZATION REPORT NUMBER

10. SPONSORING/MONITORING AGENCY REPORT NUMBER

F49620-00-1-0249

12a. DISTRIBUTION AVAILABILITY STATEMENT

APPROVED FOR PUBLIC RELEASE, DISTRIBUTION UNLIMITED

12b. DISTRIBUTION CODE

13. ABSTRACT (Maximum 200 words)

THE DURIP AWARD WAS USED TO PURCHASE TWO PIECES OF INSTRUMENTATION IN SUPPORT OF ONE OVERREACHING GOAL OF THE AFOSR FUNDED PROGRAM: CORRELATION OF GROWTH CONDITIONS OF SILICON CARBIDE BOULES AND THEIR STRUCTURAL CHARACTERISITICS.

20031006 072

**14. SUBJECT TERMS** 

**15. NUMBER OF PAGES** 

**16. PRICE CODE** 

17. SECURITY CLASSIFICATION OF REPORT

18. SECURITY CLASSIFICATION OF THIS PAGE 19. SECURITY CLASSIFICATION OF ABSTRACT

20. LIMITATION OF ABSTRACT

UNCLASSIFIED

UNCLASSIFIED

UNCLASSIFIED

20. 2.......

Standard Form 298 (Rev. 2-89) (EG) Prescribed by ANSI Std. 239.18 Designed using Perform Pro, WHS/DIOR, Oct 94

Final Technical NE

Grant title:

"DURIP: Acquisition of Single and Double Crystal X-Ray

Topography System".

Grant Number:

F49620-00-1-0249

Funding Agency:

**AFOSR** 

Award period:

03/28/2000 -06/30/2001

The DURIP award was used to purchase two pieces of instrumentation in support of one overreaching goal of the AFOSR funded program: correlation of growth conditions of silicon carbide boules and their structural characteristics.

The x-ray topography unit was ordered in September of 2000 and manufactured and delivered to Carnegie Mellon University in January of 2001. The installation was completed in March 2001 and was followed by extensive alignment and testing. The photograph of the system is shown in Fig. 1

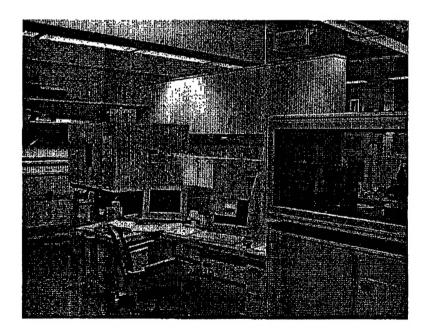


Fig. 1 X-ray topography system installed in Wean Hall 8302. The cabinet on the left side houses Lang camera, cabinet on left encloses the double crystal topography unit.

DISTRIBUTION STATEMENT A Approved for Public Release Distribution Unlimited

The system is producing valuable data for several federally funded projects including:

- 1. "Growth of semi-insulating 6H-SiC crystals for GaN-based microwave devices" funded by Air Force Research Laboratory, POC: L. S. Rea, phone: (937) 255-4474 ext. 3213, principal investigator: M. Skowronski
- 2. "Structural defects in semi-insulating SiC wafers" funded by Air Force Office of Scientific Research, POC: Maj. D. Johnstone, phone: (703) 696-7545, principal investigator: M. Skowronski
- 3. "High Volume, High Quality Silicon Carbide Substrate Merchant Manufacturing" subcontract to Sterling Semiconductor, Inc., "Three Inch SiC substrate manufacturing", subcontract to Airtron Litton Corporation, Air Force Title III program, POC: J. Blevins, Air Force Research Laboratory, (937) 255-3701 ext. 226, principal investigator: M. Skowronski
- 4. "Identification of Screw Dislocation Sources in SiC PVT Growth" funded by Office of Naval Research, POC: C. E. Wood, phone: (703) 696-4218, PI: M. Skowronski
- 5. "Mechanisms of Extended Defect Nucleation during PVT Growth of Silicon Carbide" funded by National Science Foundation, POC: L. Hess, (703) 292-4937, PI: M. Skowronski

The system is intensively used for imaging extended defects in silicon carbide crystals grown by Physical Vapor Transport method and in silicon carbide high voltage diodes. Among the major findings accomplished with the help of x-ray topography are:

- Evidence of plastic deformation occurring during crystal growth of SiC boules. This
  effect causes the dislocation multiplication and resulting densities in the 10<sup>5</sup> cm<sup>-2</sup>
  range.
- 2. Evidence of dislocation serving as nucleation sites for stacking faults under forward bias. This leads to the degradation of SiC bipolar devices through increase of forward voltage drop. Both the stacking faults and pre-existing dislocations have been imaged using x-ray topography.
- 3. Evidence of stacking faults formation during initial stages of SiC growth leading to nucleation of screw dislocations. These defects are known to reduce the intrinsic

breakdown voltage of silicon carbide through formation of isolated microplasmas. Current density of screw dislocations in state-of-the-art wafers is above  $10^3$  cm<sup>-3</sup>. Carnegie Mellon University demonstrated growth approaches resulting in densities as low as  $10^1$  cm<sup>-2</sup>.

The example of a x-ray topograph obtained using the system acquired with AFOSR funds is shown in Fig. 2. The inclined lines forming 600 angle correspond to two sets of basal plane dislocations with Burgers vectors of a/3<11-20> and a/3<2-110>.

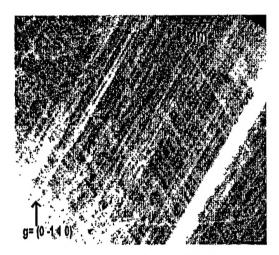


Fig. 2 X-ray topograph of a high quality 4H-SiC wafer with straight basal plane dislocation segments.

The RF power supply was purchased from Mesta Electronics and delivered in March 2001. It has been used since in the silicon carbide growth effort producing crystals used programs listed above. It is also expected that the inverter will contribute to the program recently funded by DARPA Wide Band Gap Initiative as part of the project on "Halide CVD SiC Growth".